

| Ref #. | Hits | Search Query | DBs | Default Operator | Plurals | Time Stamp |
|--------|-------|---|--|------------------|---------|------------------|
| L1 | 98331 | (photosensitive or photoresist or photolithographic or lithographic) same (resin or polymer or copolymer) | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/11/19 07:39 |
| L2 | 872 | polybenzoxazole same (polyimide or hydroxypolyamide) | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/11/19 08:11 |
| L3 | 228 | 1 and 2 | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/11/19 08:12 |

Refine Search

Search Results -

| Terms | Documents |
|-----------------------|-----------|
| Jp-2002012665-\$.did. | 2 |

Database: US Pre-Grant Publication Full-Text Database
US Patents Full-Text Database
US OCR Full-Text Database
EPO Abstracts Database
JPO Abstracts Database
Derwent World Patents Index
IBM Technical Disclosure Bulletins

Search:

L1

Refine Search

Recall Text  Clear  Interrupt 

Search History

DATE: Friday, November 19, 2004 [Printable Copy](#) [Create Case](#)

| <u>Set Name</u> | <u>Query</u> | <u>Hit Count</u> | <u>Set Name</u> |
|--|-----------------------|------------------|-----------------|
| side by side | | | result set |
| DB=PGPB,USPT,USOC,EPAB,JPAB,DWPI,TDBD; PLUR=YES; OP=OR | | | |
| <u>L1</u> | Jp-2002012665-\$.did. | 2 | <u>L1</u> |

END OF SEARCH HISTORY

Hit List

| | | | | |
|---------------|---------------------|-------|----------|-----------|
| Clear | Generate Collection | Print | Fwd Refs | Bkwd Refs |
| Generate OACS | | | | |

Search Results - Record(s) 1 through 2 of 2 returned.

1. Document ID: JP 2002012665 A

Using default format because multiple data bases are involved.

L1: Entry 1 of 2

File: JPAB

Jan 15, 2002

PUB-NO: JP02002012665A

DOCUMENT-IDENTIFIER: JP 2002012665 A

TITLE: PHOTORESISTIVE RESIN AND COMPOSITION THEREOF

PUBN-DATE: January 15, 2002

INVENTOR-INFORMATION:

| NAME | COUNTRY |
|---------------------|---------|
| KANEDA, TAKAYUKI | |
| KIMURA, MASASHI | |
| KANETANI, RYUICHIRO | |

INT-CL (IPC): C08 G 73/22; C08 K 5/00; C08 L 79/06; G03 F 7/038; G03 F 7/40; H01 L 21/027

| | | | | | | | | | | | | | | |
|------|-------|----------|-------|--------|----------------|------|-----------|--|--|--|--|--------|-----|----------|
| Full | Title | Citation | Front | Review | Classification | Date | Reference | | | | | Claims | KMC | Drawn De |
|------|-------|----------|-------|--------|----------------|------|-----------|--|--|--|--|--------|-----|----------|

2. Document ID: JP 2002012665 A

L1: Entry 2 of 2

File: DWPI

Jan 15, 2002

DERWENT-ACC-NO: 2002-540892

DERWENT-WEEK: 200258

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TITLE: Photosensitive polybenzoxazole precursor resin preparation for insulating material of electronic parts, comprises reacting part of hydroxyl group in hydroxypolyamide with unsaturated double bond-having isocyanate compound

| | | | | | | | | | | | | | | |
|------|-------|----------|-------|--------|----------------|------|-----------|--|--|--|--|--------|-----|----------|
| Full | Title | Citation | Front | Review | Classification | Date | Reference | | | | | Claims | KMC | Drawn De |
|------|-------|----------|-------|--------|----------------|------|-----------|--|--|--|--|--------|-----|----------|

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| Print | Fwd Refs |
| Bkwd Refs | Generate OACS |

| | |
|-------|-----------|
| Terms | Documents |
| | |